



8-1-01
Pro. Am. H. A.
N. Entered
Docket No. 8733.378.00

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re application of

Myoung-Su YANG

Group Art Unit: TBA

Serial No.: 09/748,871

Examiner: TBA

Filed: **December 28, 2000**

For: **Method of Forming a Polycrystalline Silicon Layer**

PRELIMINARY AMENDMENT

Assistant Commissioner of Patents
Washington, D.C. 20231

Sir:

Prior to issuance of a first Office Action, please amend the above-referenced application as follows:

IN THE SPECIFICATION:

Applicants hereby respectfully submit a Substitute Specification, along with a CompareRite document showing all of the deletions and additions.

IN THE DRAWINGS:

A proposed drawing change accompanies this Preliminary Amendment. That proposed drawing change deletes the heading for Fig. 1B, and amends the title of Fig. 1C to Fig. 1B. These proposed changes are aimed at clarifying the drawings.

IN THE CLAIMS:

Please **ADD** new Claims 7-17 as follows:

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- 7. A method of forming a polycrystalline silicon layer, comprising:
forming an amorphous silicon layer on a substrate;